

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	source near power near greater near frequency near bias	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 11:39
L2	0	(source near power) near (greater near frequency) near bias	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 11:40
L3	26	(source near power) same (greater near frequency) same bias	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 11:44
L4	2	"4,874,494".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 11:43
L5	41	bias near lower near frequency	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 11:45
L6	6	5 and (source near frequency)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 11:45
S1	3429016	plasma adj etch or MERIE or etch\$4 or remove\$4 or roughen\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:31
S2	669365	(carbon adj doped adj silicon adj dioxide) or (low adj (k or constant or konstant)) or dielectric or (OSG or organosilicate) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 07:26
S3	490780	(Fluorine adj rich or fluor\$4) or (CF4 or CFx or CFn or CFsubx or CFsubn or "CF.subx" or "CF.subn" or "CF.sub.x" or "CF.sub.n")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:34

S6	936840	(nitrogen or nitrogen\$3 or N2 or Nx or Nn or Nsubx or Nsubn or "N.subx" or "N.subn" or "N.sub.x" or "N.sub.n") or (NH3 or NHx or NHNH or NHsubx or NHsubNH or "NH.subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH") or (NF3 or NFx or NFNF or NFsubx or NFsubNF or "NF.subx" or "NF.subNF" or "NF.sub.x" or "NF.sub.NF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:18
S7	13446	(hydrogen adj rich) or (hydrofluorocarbon or hydrofluoro\$5)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:36
S8	40	"C.sub.2F.sub.8"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:05
S9	60	C2F8 or "C.sub.2F.sub.8" or "C.sub.xF.sub.x"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:32
S12	62	C2F8 or "C.sub.2F.sub.8" or "C.sub.xF.sub.x" or "C.sub.nF.sub.n" or "C.sub.xF.sub.n" or "C.sub.nF.sub.x"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:08
S16	1630741	(ARC or anti adj resistant adj coat or anti adj reflection adj coat) OR (BARC or bottom adj anti adj resistant adj coat or bottom adj anti adj reflection adj coat) OR (Silicon adj Dioxide) or (Riston or dry-film adj riston adj photoresists or Riston adj\$4 DuPont)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:27
S17	298355	S1 and S2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:28
S18	199224	S3 and S6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:27
S19	2	S7 and S8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:27

S20	60	S9 and S12	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:28
S22	33811	S1 and S2 and S18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:29
S23	2	S1 and S2 and S18 and S19 and S20	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:29
S24	62	S9 or S12	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:30
S25	490805	S9 or S12 or S3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:30
S26	2826662	(inert adj gas) or (inert) or (argon or Ar) or (helium or He )or (neon or Ne) or (xenon or xe)or (krypton or Kr)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:32
S27	419	S1 and S2 and S25 and S6 and S7 and S26 and S16	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:47
S28	918042	Coral or Black Diamond or benzocyclobutene or parylene or polytetrafluoroethylene or polyether or polyimide	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:35
S29	270	S27 and S28	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:42
S30	1	S1 same S2 same S25 same S6 same S7 same S26 same S16	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:36

S31	2	S29 and vhf	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:46
S32	1	10/632873	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:47
S33	1	(S1 and S2 and S25 and S6 and S7 and S26 and S16).ab.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 08:52
S34	13	(plasma adj etch) and fluorine and N2 and hydrofluorocarbon	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 10:16
S35	0	(plasma adj etch) same fluorine same N2 same hydrofluorocarbon	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 10:16
S36	2	"6828251"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/24 15:06
S38	1	10/632873	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 07:32
S39	0	("6410437,6362109,6346482, 6168726,5707486").pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 07:33
S40	10	"6410437".pn. "6362109".pn. "6346482".pn. "6168726".pn. "5707486".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 07:53
S42	37851	fluor\$4 and nitro\$4 and hydro\$4 and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 07:54

S43	12136	S42 and ((silicon adj dioxide) or (SiO2 or SiOx or SiOn or "SiO.sub2" or "SiO.subx" or "SiO.subn" or "SiO.sub.2" or "SiO.sub.x" or "SiO.sub.n"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 07:55
S44	1067	S43 and etch adj rate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 07:55
S45	138	S44 and pedestal	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 07:55
S46	38	S45 and DC adj bias	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 11:18
S47	2	"6,410,451".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/25 11:18
S48	2	"6451703".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:58
S49	601	MERIE	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:56
S50	72004	(Applied Materials, "Inc.").as.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:59
S51	103	S49 and S50	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 09:02
S52	11	S49 and S50 and (overhead near electrode)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 10:02

S53	1	"6894245".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 10:26
S54	2	"6869542".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 11:16
S55	37	fuor\$4 and nitro\$4 and hydro\$4 and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 11:00
S56	95	CH2F2 and CF4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 11:01
S57	59	S56 and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 11:07
S58	55	S57 and etch	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 11:01
S59	38	S56 and plasma and dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 11:12
S60	2	"6287978".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 11:13
S61	2	"6828251".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:46
S62	2	"6894245".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:31

S63	1	10/632873	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:43
S64	2	"6869542"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:43
S65	0	"645170.pn"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:47
S66	0	"6451703.pn"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:49
S67	0	"6451703.pn."	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:49
S68	2	"6451703".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/07/08 13:49
S69	14739	(hydrogen adj rich) or (hydrofluorocarbon or hydrofluoro\$5) or (CH2F2 or CHxFx or CHnFn or CHsubxFsubx or CHsubnFsubn or "CH.subxF.subx" or "CH.subnF.subn" or "CH.sub.xF.sub. x" or "CH.sub.nF.sub.n")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:36
S70	515125	(Fluorine adj rich or fluor\$4) or (CF4 or CFx or CFn or CFsubx or CFsubn or "CF.subx" or "CF.subn" or "CF. sub.x" or "CF.sub.n")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:37
S71	979866	(nitrogen or nitrogen\$3 or N2 or Nx or Nn or Nsubx or Nsubn or "N. subx" or "N.subn" or "N.sub.x" or "N.sub.n") or (NH3 or NHx or NHNH or NHsubx or NHsubNH or "NH. subx" or "NH.subNH" or "NH.sub.x" or "NH.sub.NH") or (NF3 or NFx or NFNF or NFsubx or NFsubNF or "NF. subx" or "NF.subNF" or "NF.sub.x" or "NF.sub.NF")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:37

S72	2880	S69 and S70 and S71	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:38
S73	10761	low near (k or constant) near dielectric	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:38
S74	1485	(rotating near magnetic near field) and (etch or etching or remove)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:39
S75	31	S73 and S74	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 08:39
S76	3	S75 and S72	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 11:39
S77	2	"6869542".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/06 09:04